

REMARKS

Favorable reconsideration is respectfully requested.

The claims are 1-17.

Claims 1, 2, 4, 5, 10, 15, and 17 are rejected under 35 U.S.C. 102(e) as being anticipated by Fujie et al (U.S. 6,303,264 B1).

This rejection is respectfully traversed.

The rejection states that the amount of surfactant in Fujie et al. converts to 10ppm by weight based on the polymer components present.

In reply, the present claims now recite an amount lower than 10 ppm. Therefore, there is no overlap with Fujie et al. in the amount of surfactant and the rejection under 35 U.S.C. 102 is clearly untenable.

The above comments are also applicable to the rejection in Official Action paragraph 5 of claim 13 as being unpatentable over Fujie et al. as well as the rejections in Official Action paragraphs 6 to 13., all of which similarly rely on Fujie et al.

The rejections in Official Action paragraph 11 over Ushirogouchi et al. in view of Fujie et al., in Official Action paragraph 12 over these references in further view of Sato et al., and in Official Action paragraph 13 over these references in further view of Padmanaban et al. will now be discussed in further detail.

As disclosed in paragraph [0008] of the present application, a principle object of the present invention is to provide a photoresist composition capable of forming a very uniform and outstandingly defect-free photoresist coating film on the substrate surface. Such object of the present invention is addressed in none of the cited references, so that the present claims are further unobvious from the cited references alone or combined.

It is noted that claim 16, while depending on claim 15, is rejected over the additional reference of Padmanaban et al. in Official Action paragraph 7, 10 and 13, however, it is clear that Padmanaban et al. does not overcome the above-discussed deficiencies of the other references with which it is combined.


For the foregoing reasons, the rejections on prior art are untenable and should be withdrawn.

No further issues remaining, allowance of this application is respectfully requested.

If the Examiner has any comments or proposals for expediting prosecution, please contact undersigned at the telephone number below.

Respectfully submitted,

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